

Correlation between Laser Absorption Process and Energy Conversion to Extreme Ultraviolet Radiation in Laser Produced Tin Plasma

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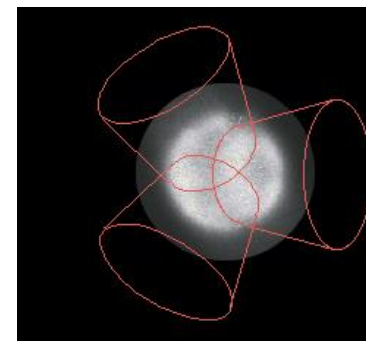
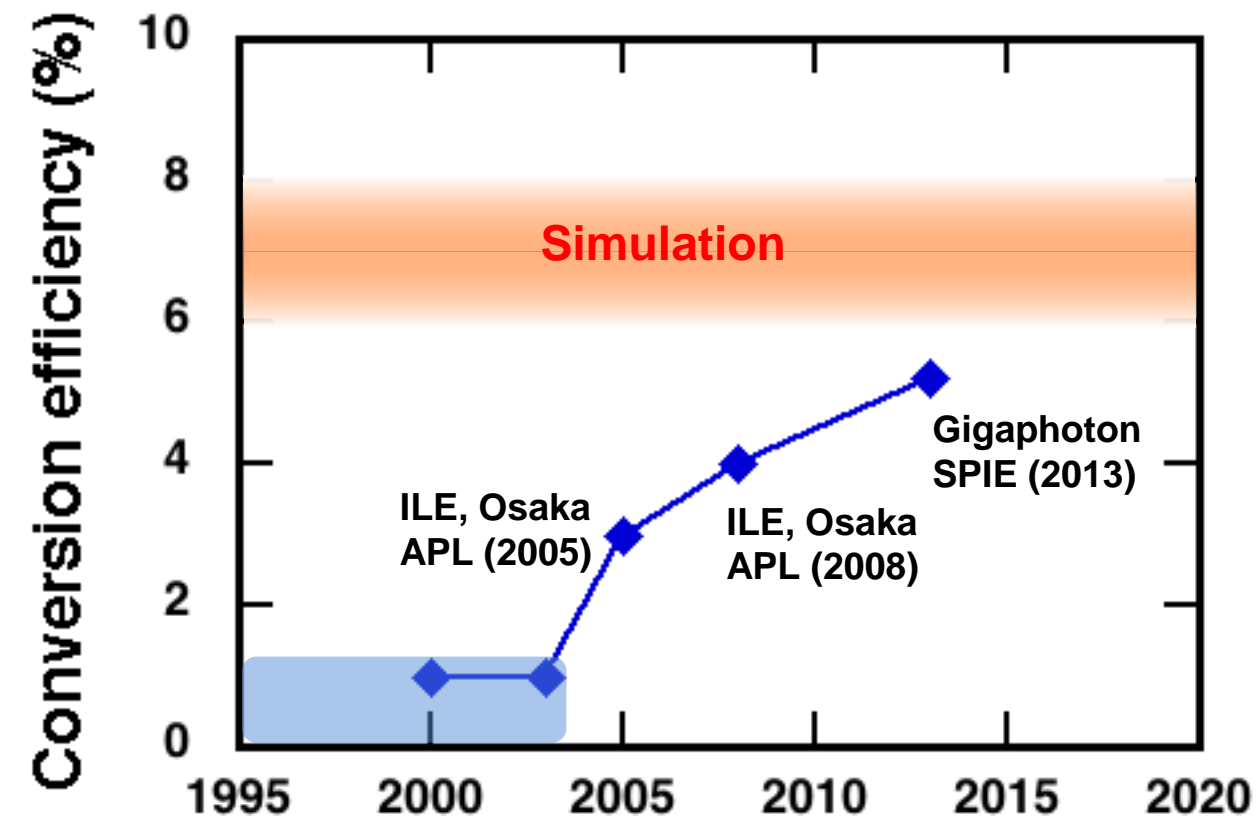
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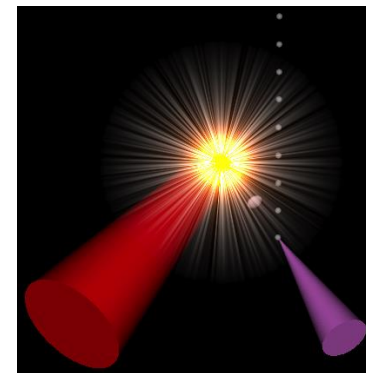
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Various studies for the highest possible conversion efficiency (CE) of EUV



Spherical (2005)

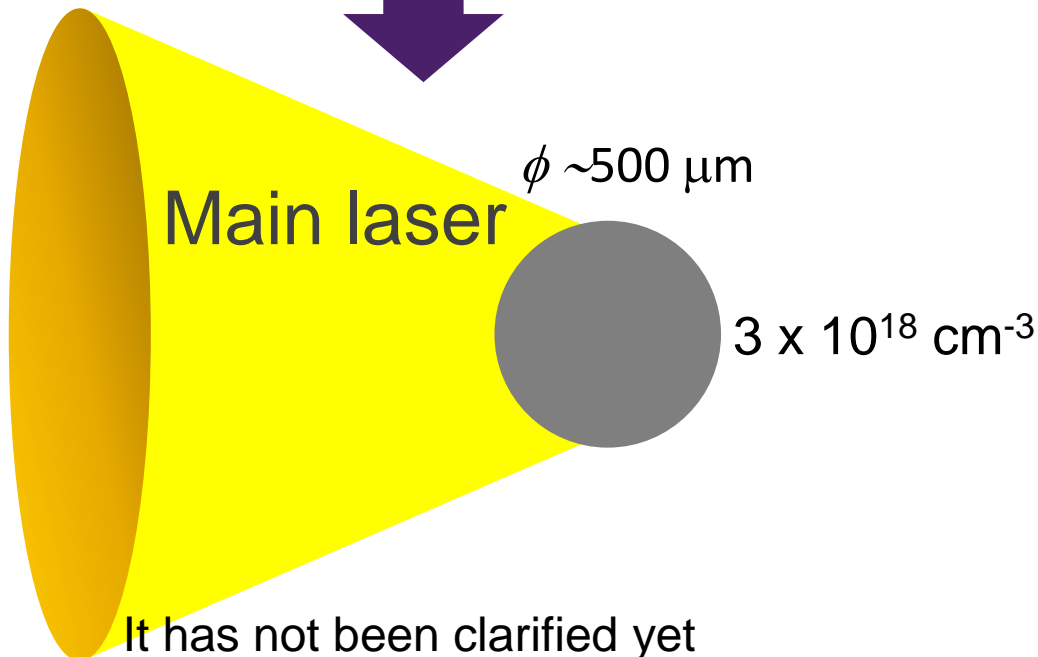
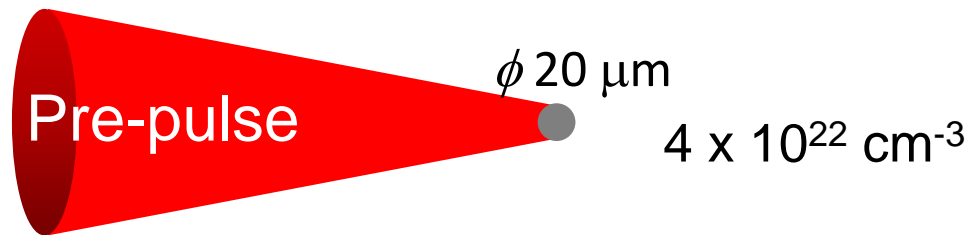


Double pulse (2008)

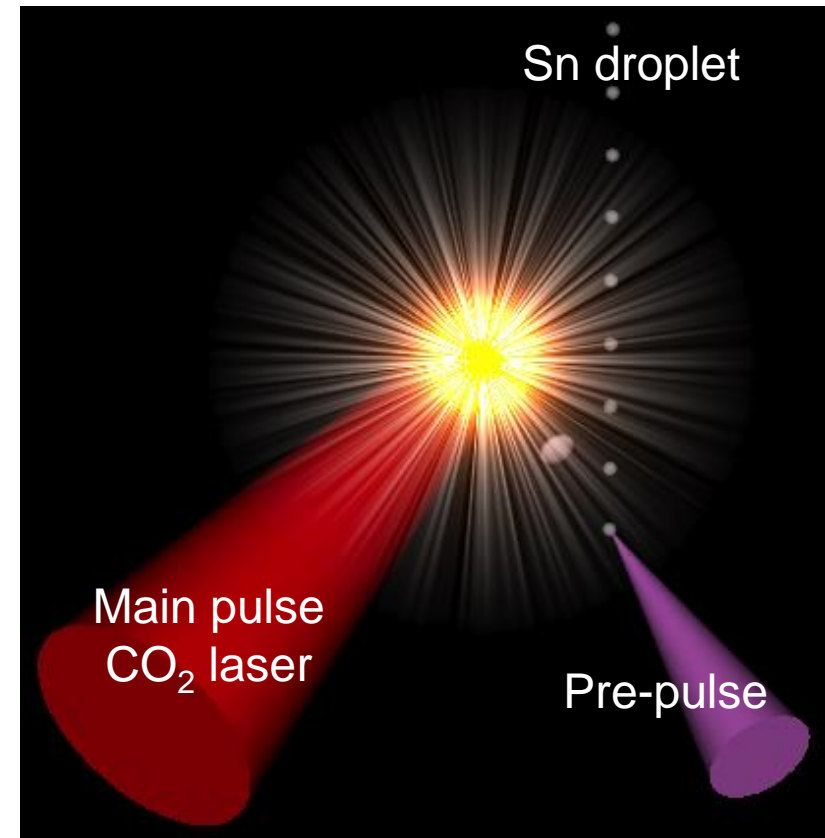
With ps pulse (2013)



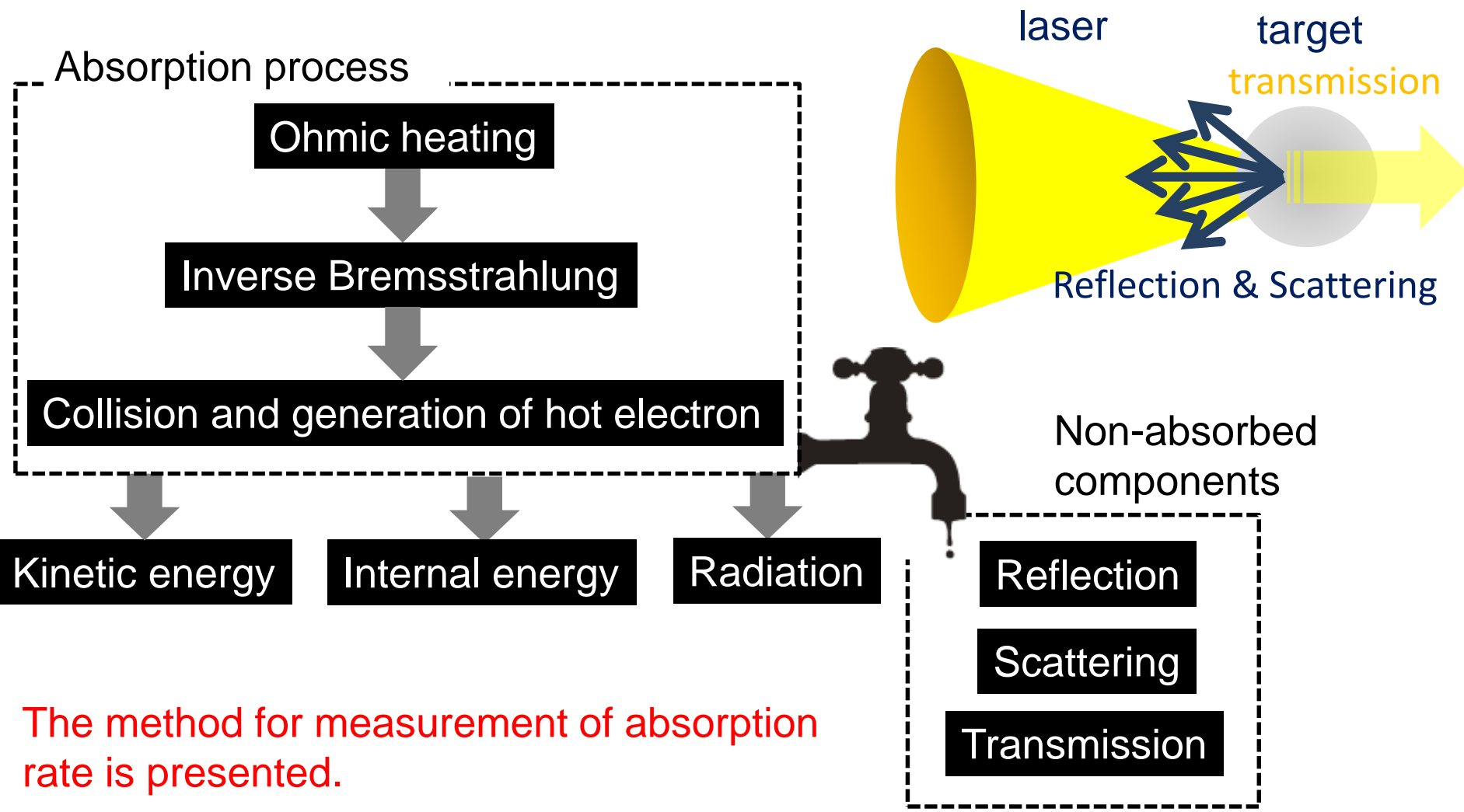
Two-color, double pulse scheme is widely adopted in EUV source for lithography



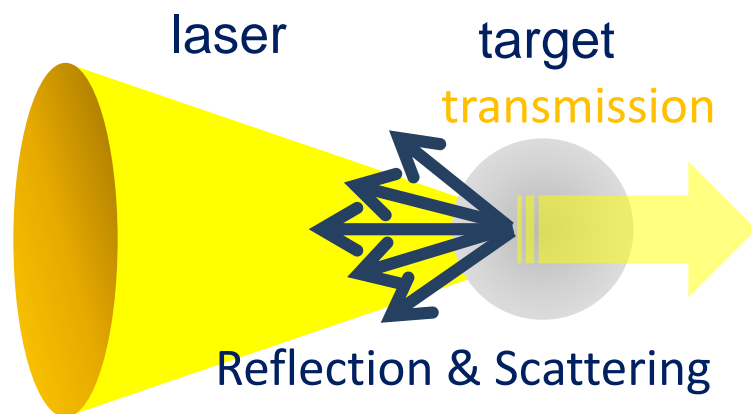
It has not been clarified yet why CE is substantially increased, optimization plasma parameters or increase in laser absorption?



Elemental processes of laser produced plasma



We developed an integrating sphere for measurement of absorption rate by plasma



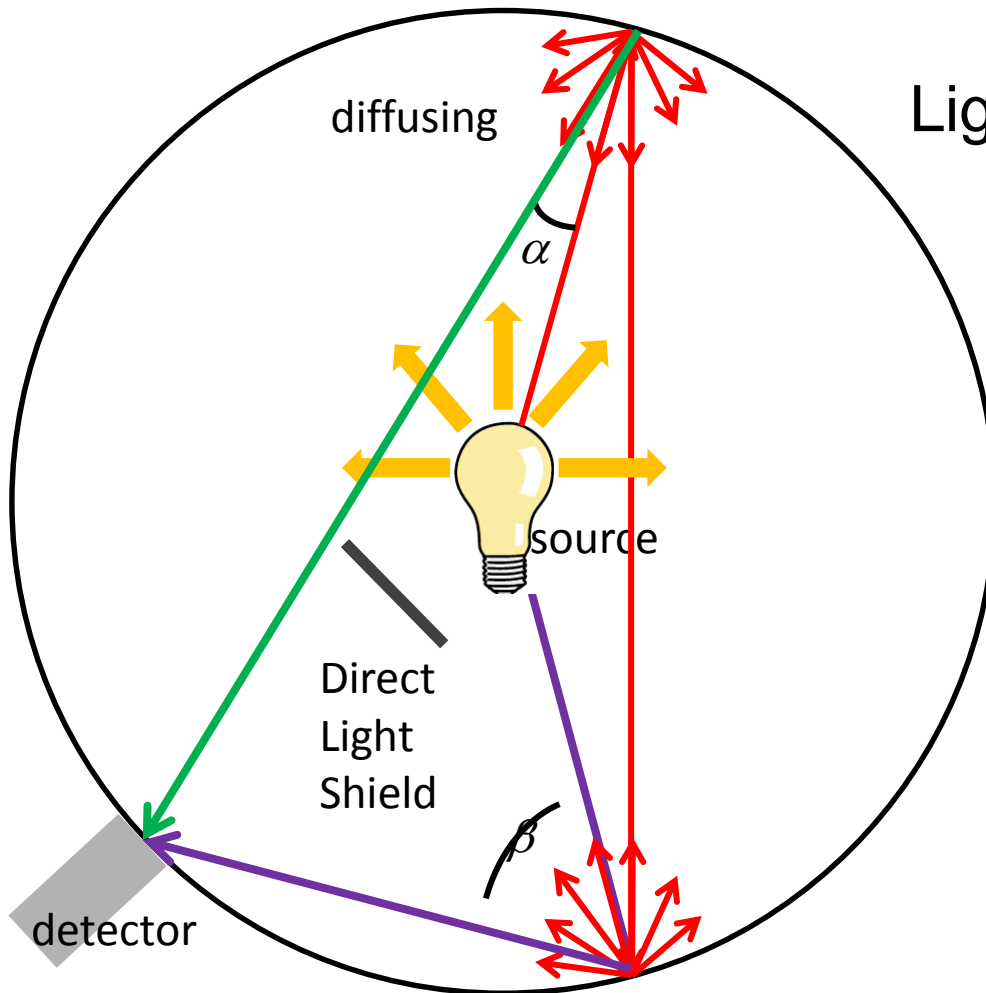
Integrating sphere

- Collecting specular and scattered light for 4π of solid angle
- NOT depending on angular distribution of light emission
- Proportional to light flux



$$\text{Absorption rate} = 1 - \frac{I_{\text{specular}} + I_{\text{scattered}}}{I_{\text{laser}}}$$

Multi-reflection of scattered light homogenizes its distribution on the inner surface



Light intensity @detector

$$= \frac{\rho \Phi}{S} (1 + \rho + \rho^2 + \rho^3 + \rho^4 + \dots + \rho^{n-1})$$

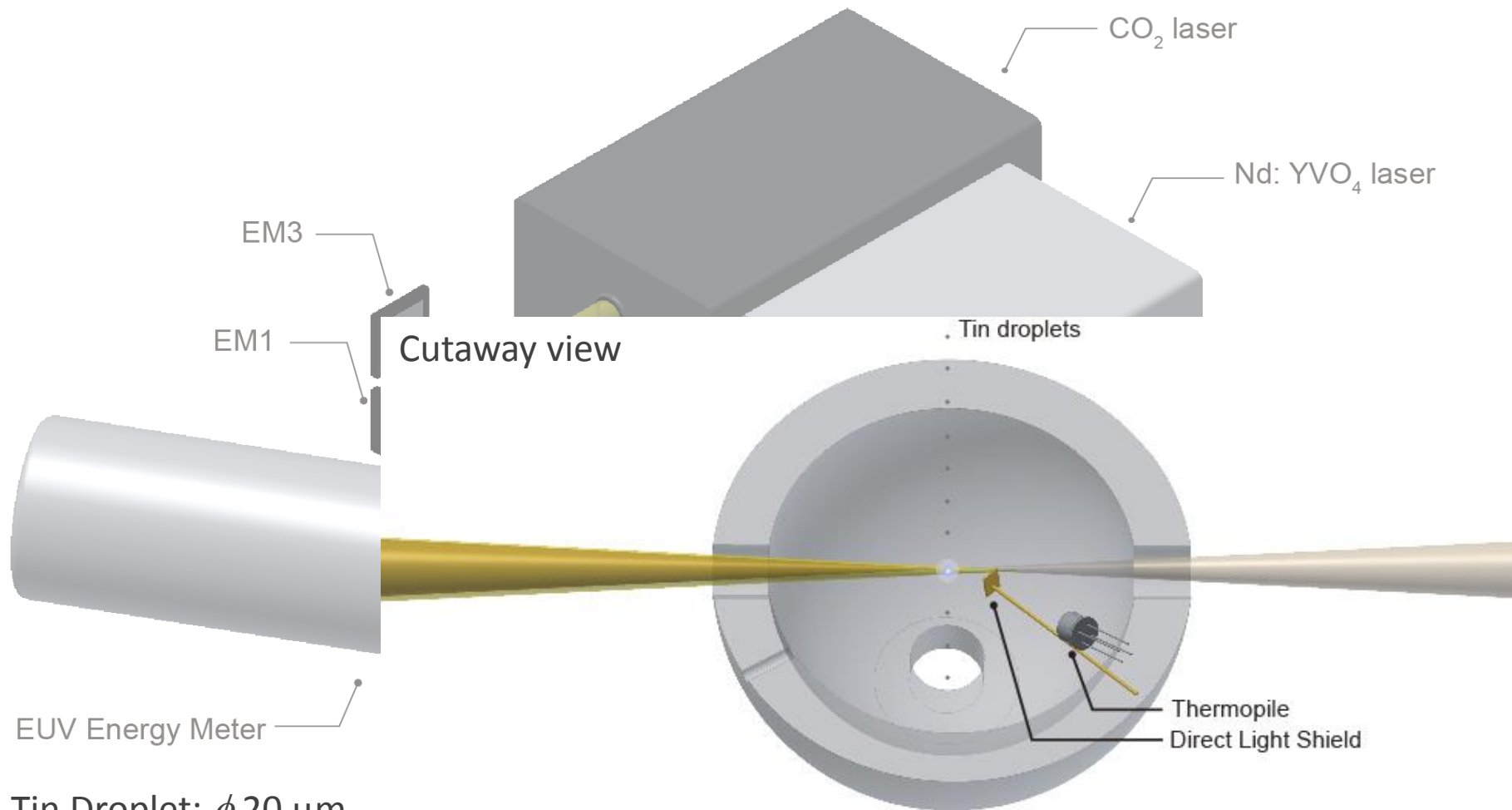
$$= \frac{\Phi}{S} \frac{\rho}{1 - \rho}$$

Φ : light source power

ρ : diffuse reflection factor

S : surface area of integrating sphere

Experimental setup

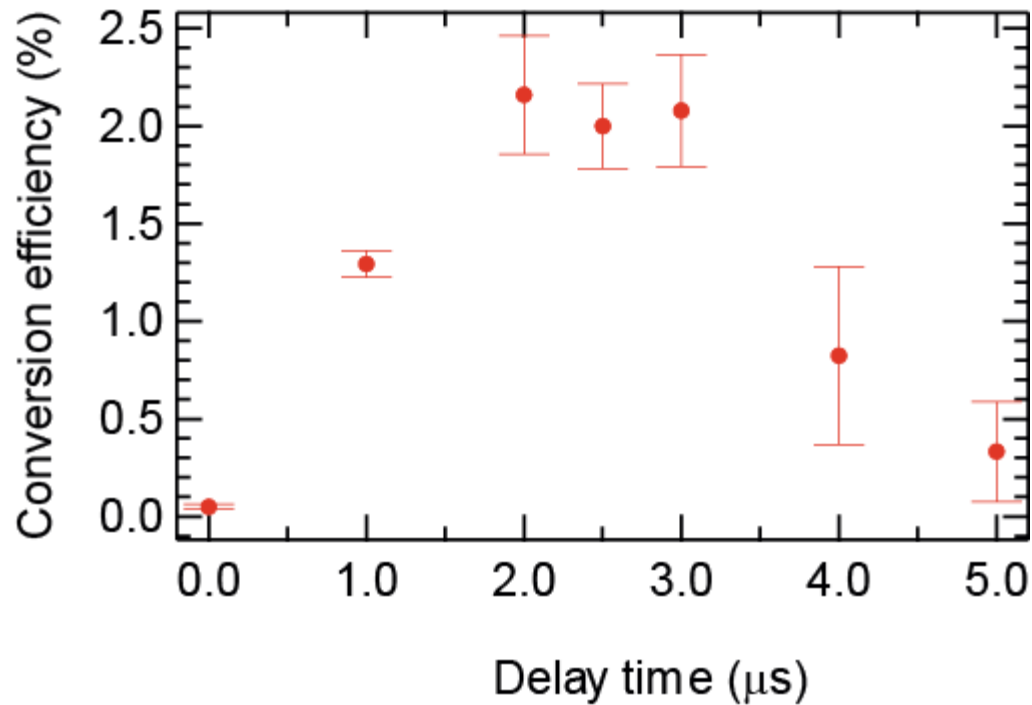


Tin Droplet: ϕ 20 μm

Nd:YVO₄ laser (Pre): $\lambda = 1064 \text{ nm}$, 14 ps, 1.9 mJ, ϕ 77 μm (intensity $I_{\text{pre}} = 2.9 \times 10^{12} \text{ W/cm}^2$)

CO₂ laser (Main): $\lambda = 10.6 \mu\text{m}$, 14 ns, 100 mJ, ϕ 400 μm (intensity $I_{\text{pre}} = 5.7 \times 10^9 \text{ W/cm}^2$)

Timing-dependence of CE



$t < 2 \mu\text{s}$

increasing

$2 < t < 3 \mu\text{s}$

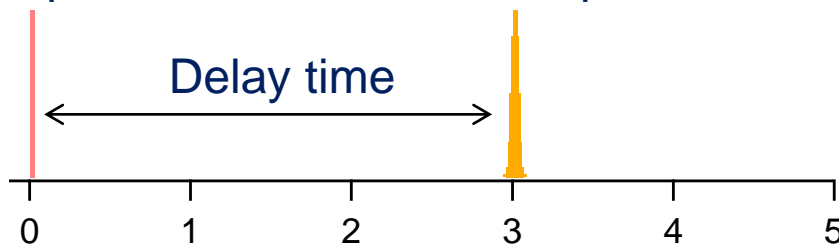
maximum

$t > 3 \mu\text{s}$

decreasing

14 ps pre-pulse

14 ns main-pulse

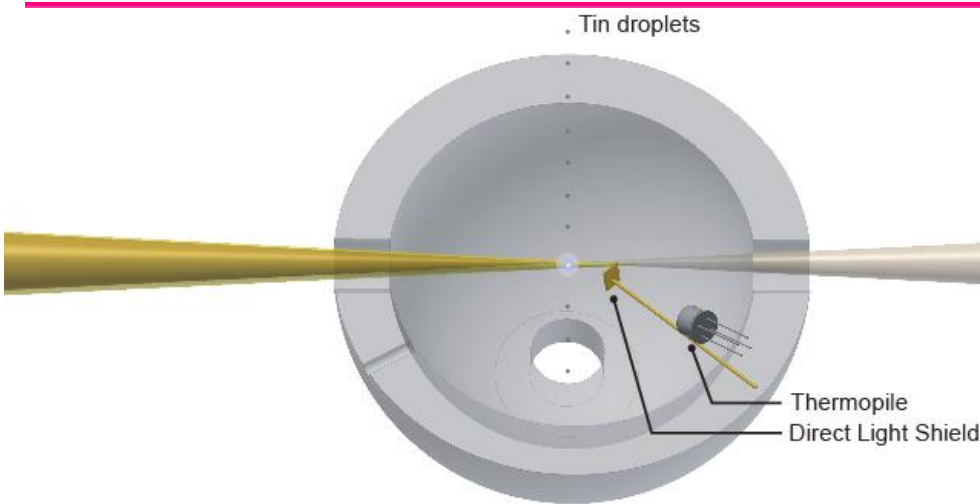


Tin Droplet: ϕ 20 μm

Pre-pulse: $\lambda = 1064 \text{ nm}$, 14 ps, 1.9 mJ, ϕ 77 μm (intensity $I_{\text{pre}} = 2.9 \times 10^{12} \text{ W/cm}^2$)

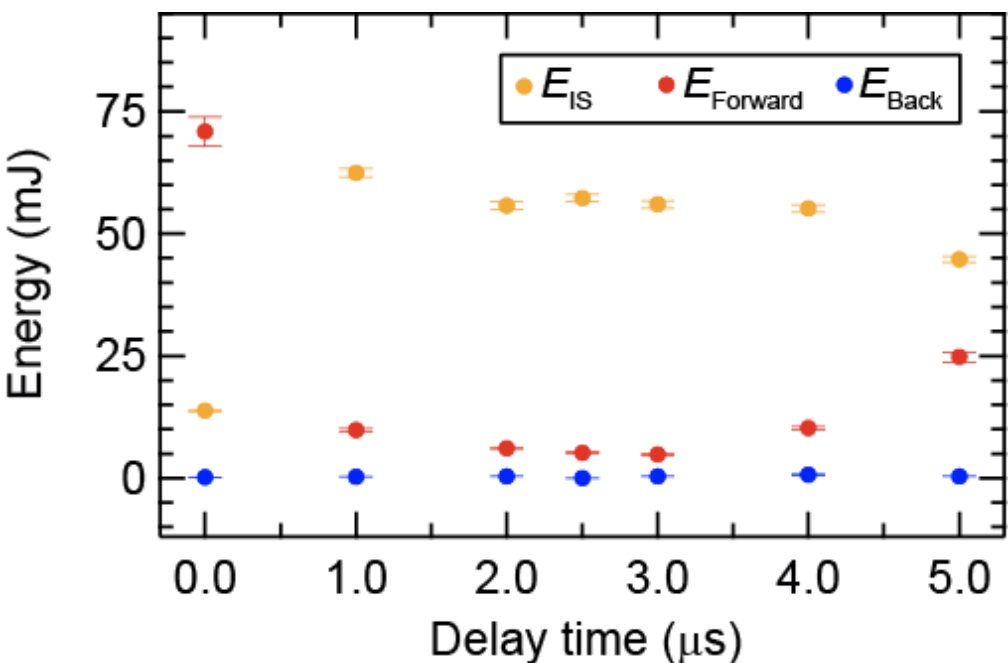
Main-pulse: $\lambda = 10.6 \mu\text{m}$, 14 ns, 100 mJ, ϕ 400 μm (intensity $I_{\text{Main}} = 5.7 \times 10^9 \text{ W/cm}^2$)

Results: scattering components



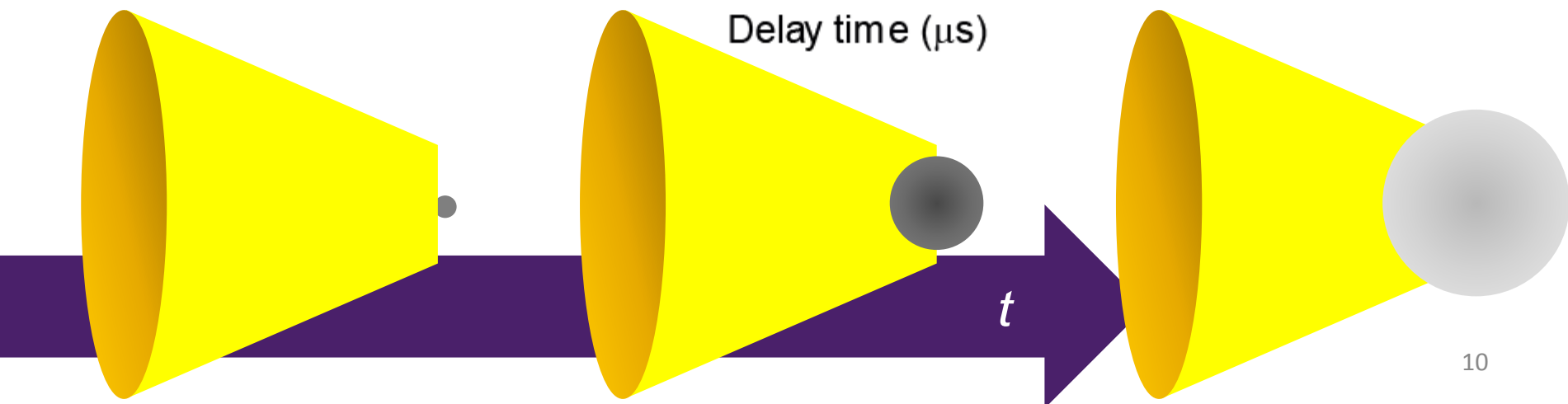
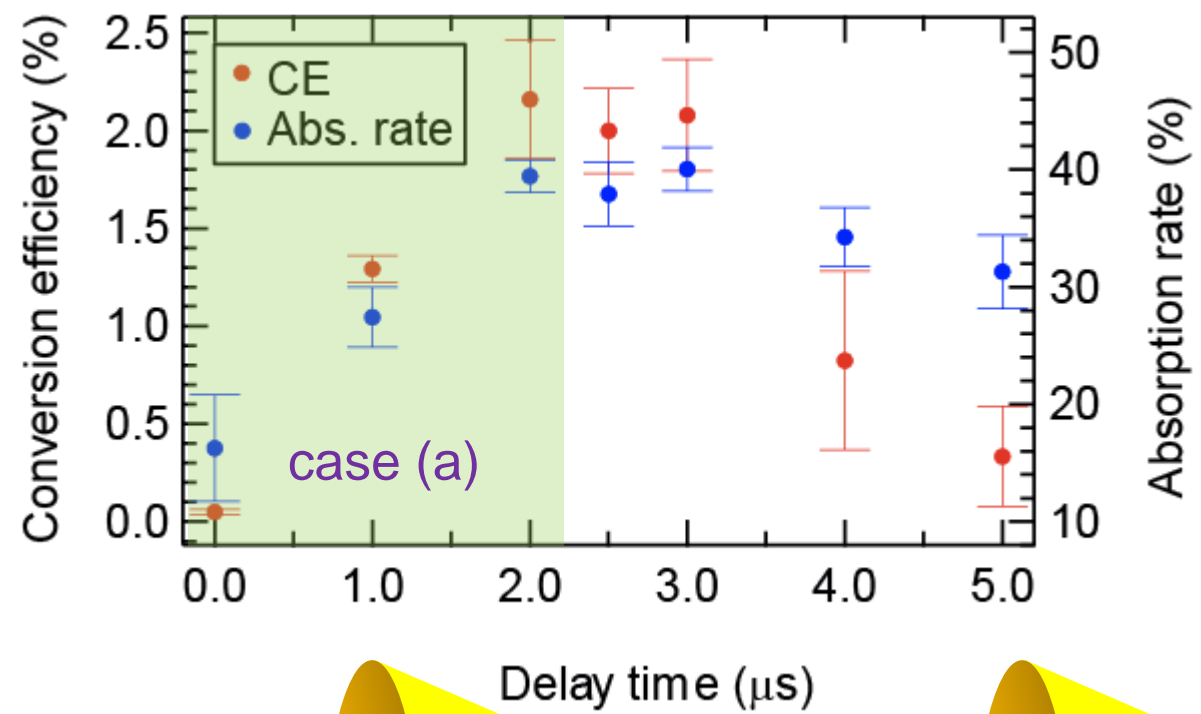
Three scattering components

- sideward E_{IS}
- transmitted $E_{Forward}$
- backward E_{Back}



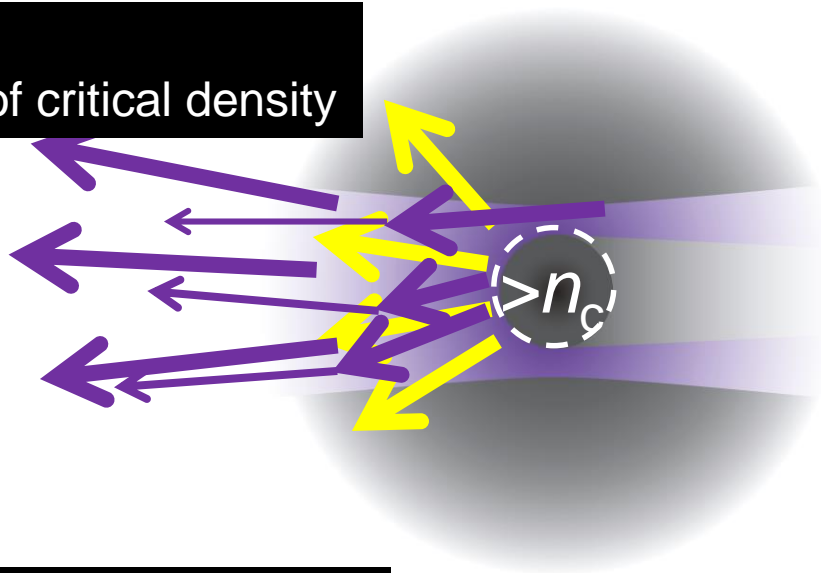
$$\begin{aligned}
 \text{Abs. rate} &= 1 - \frac{I_{\text{specular}} + I_{\text{scattered}}}{I_{\text{laser}}} \\
 &= 1 - \frac{E_{IS} + E_{Forward} + E_{Back}}{E_{Laser}}
 \end{aligned}$$

Absorption rate correlates with CE strongly
,but CE decreases rapidly for longer interval

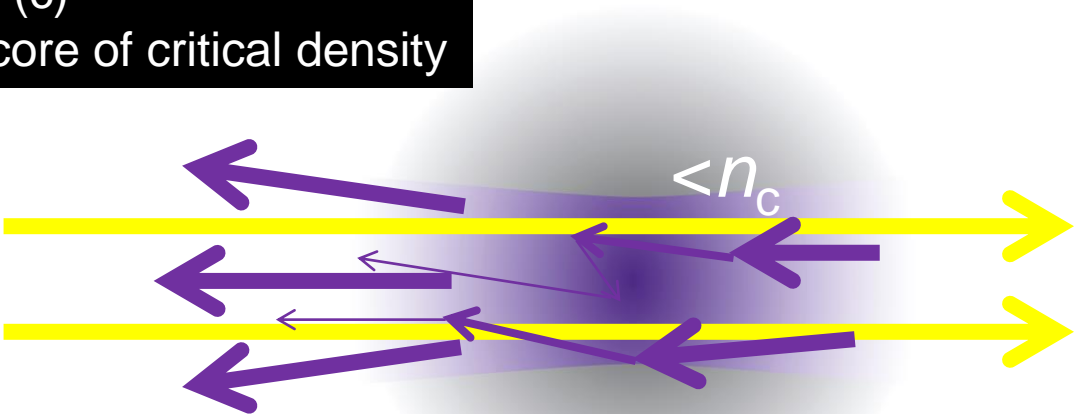


CE decreases with longer interval of double pulses

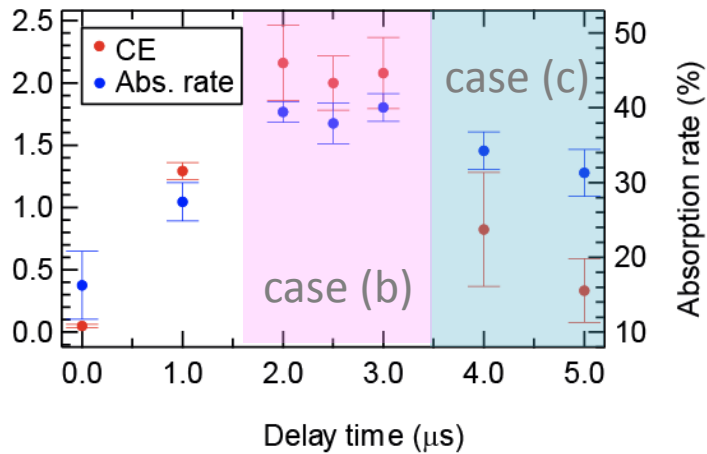
case (b)
w/ core of critical density



case (c)
w/o core of critical density



CO₂ laser



Laser penetrates deeper

Generation of optical thick plasma for EUV

EUV is converted to kinetic energy

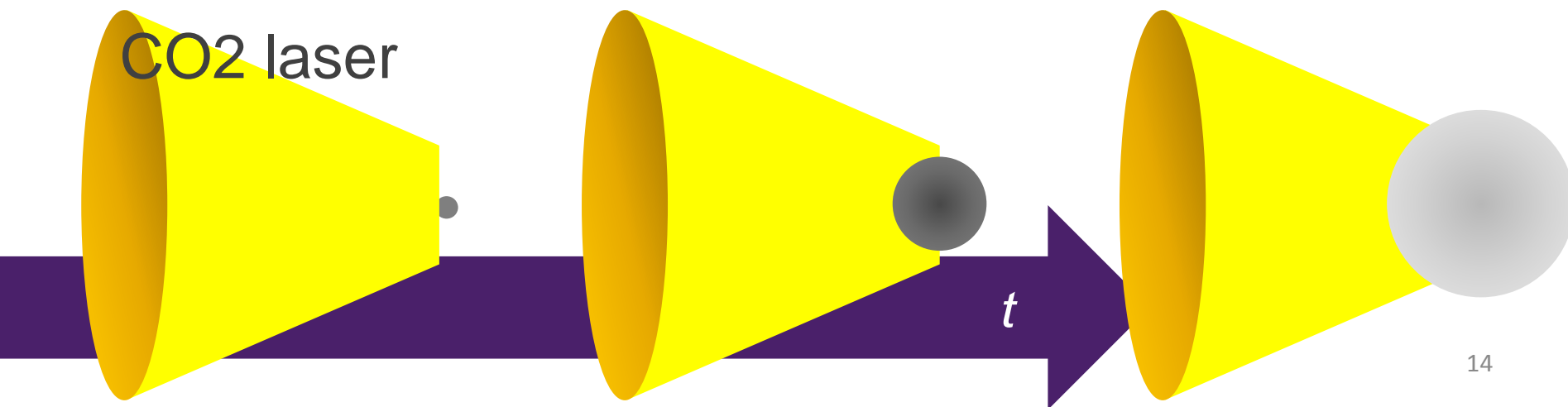
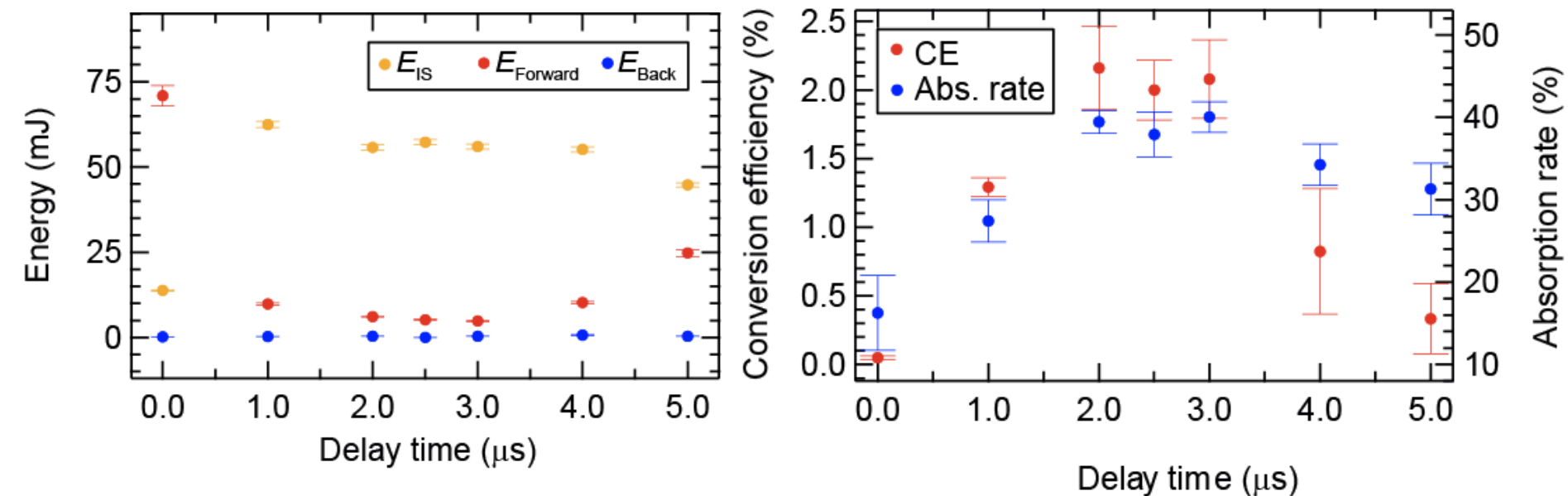
Decreasing effective EUV

Summary

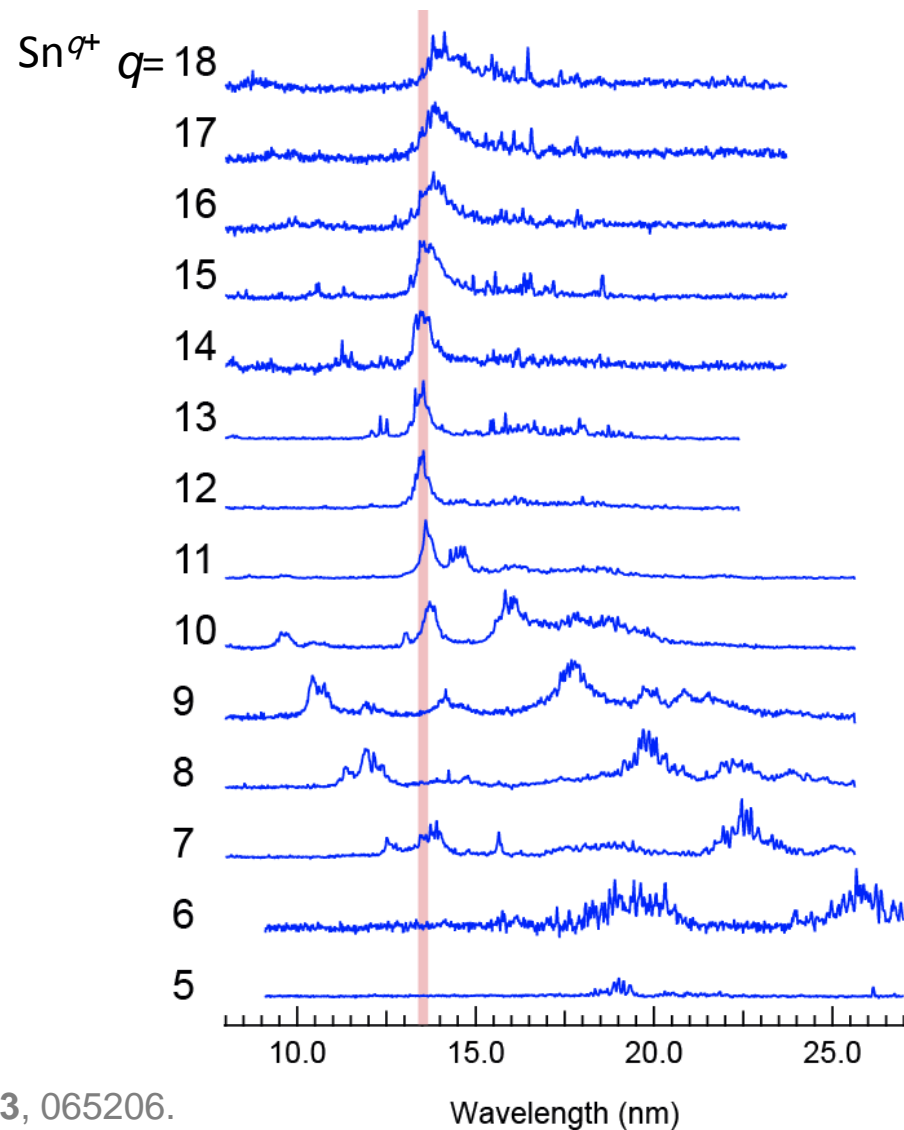
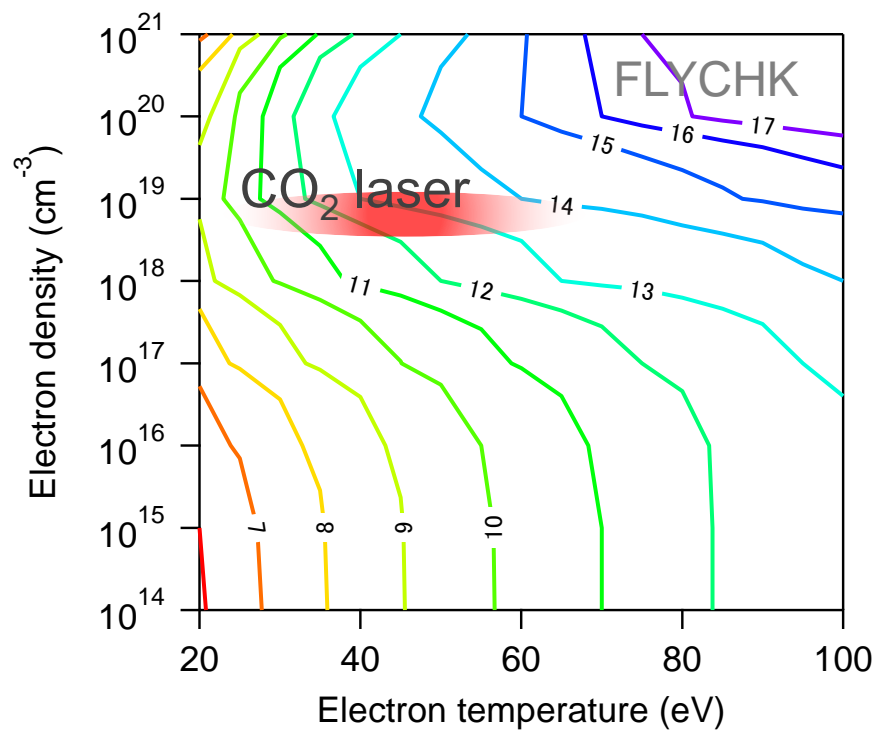
- ✓ To study correlation between laser absorption rate and CE, we developed an integrating sphere for CO₂ laser
- ✓ EUV CE at 13.5 nm and the drive laser absorption rate was measured
- ✓ It is effective for improving EUV CE to increase laser absorption rate.
- ✓ Optimization of optical depth is also necessary
- ✓ A density of plasma core should be larger than critical density of drive laser for increasing absorption rate and decreasing optical depth

Appendix

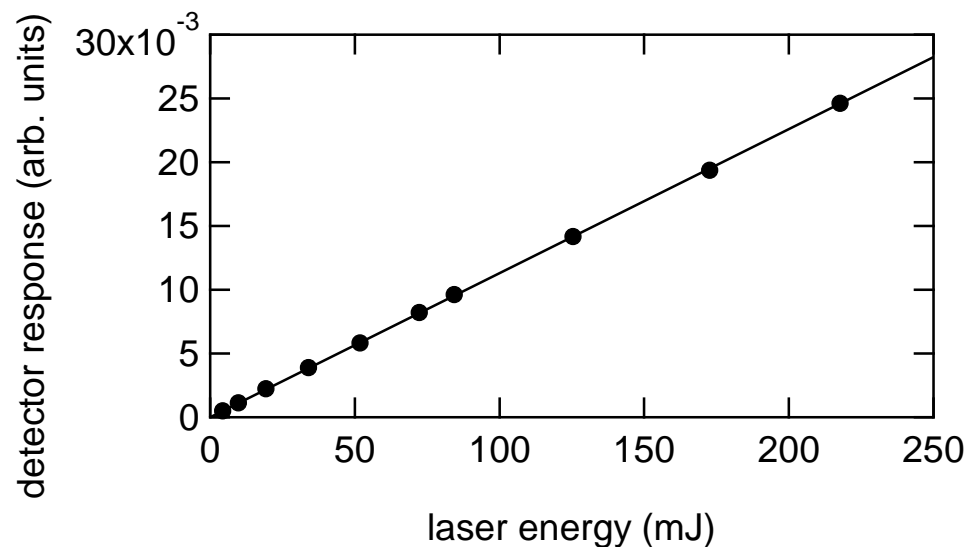
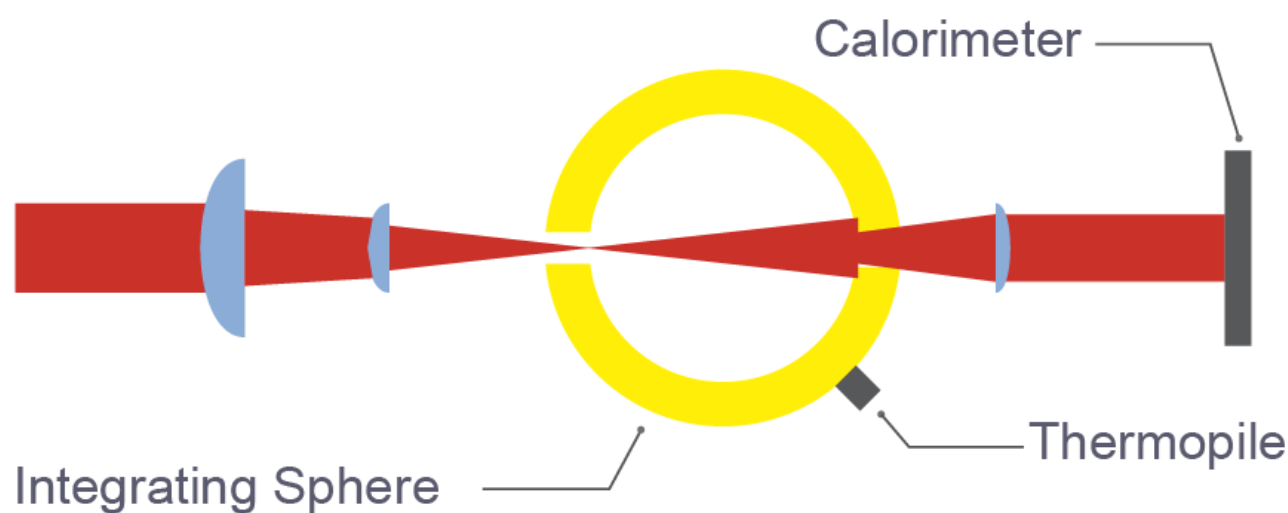
Scattering direction



Unresolved transition array at 13.5 nm



Calibration

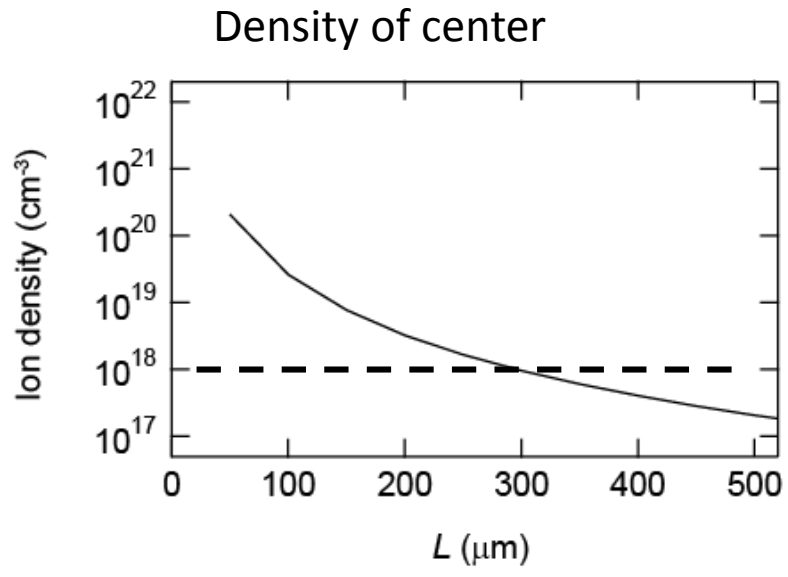
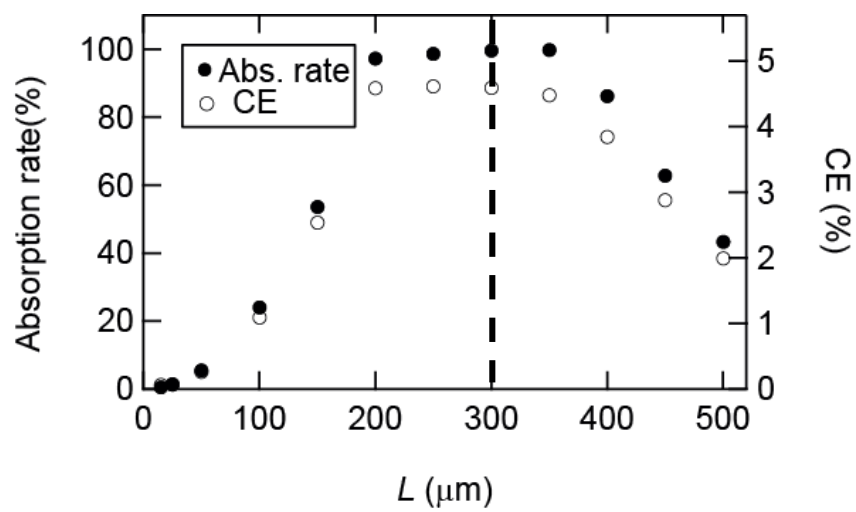


Comarison with Simulation

Assuming Gaussian profile of initial ion density

$$\rho(r) = \rho_0(L) \exp\left\{-\left(r/L\right)^2\right\}$$
$$\int_0^\infty \rho_0(L) \exp\left\{-\left(r/L\right)^2\right\} \times 4\pi r^2 dr = N$$

1-D simulation results

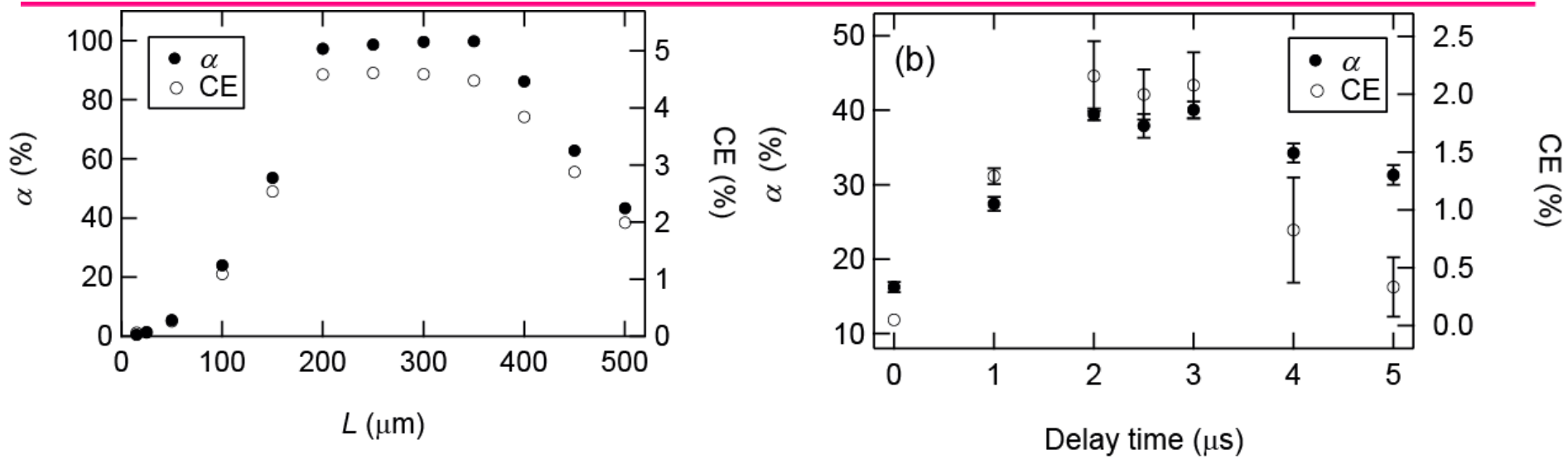


10—15 times ionized tin emits EUV

→critical density for CO₂ laser is estimated around 10¹⁸ cm⁻³ of ion density

→laser transmits plasma

Comparison with simulation



Twice larger than
experimental results

